



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

**Tamihide YASUMOTO**

Group Art Unit: **2813**

Serial No.: **09/995,575**

Examiner: **KIELIN, Erik J.**

Filed: **November 29, 2001**

Confirmation No.: **1497**

For: **SEMICONDUCTOR DEVICE MANUFACTURING METHOD USING METAL  
SILICIDE REACTION AFTER ION IMPLANTATION IN SILICON WIRING**

Attorney Docket No.: **011317**

Customer Number: **38834**

**SUBMISSION UNDER 37 C.F.R. §1.114**

Mail Stop RCE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

February 9, 2004

Sir:

This Submission is being filed concurrently with a Request for Continued Examination pursuant to 37 C.F.R. §1.114. Please amend the application as follows.

**Amendments to the Specification** begin on page 2 of this paper.

**Amendments to the Claims** are reflected in the list of claims which begins on page 3 of this paper.

**Amendments to the Drawings** begin on page 7 of this paper and include both an attached replacement sheet and an annotated sheet showing changes.

**Remarks/Arguments** begin on page 8 of this paper.

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